

**Notice of References Cited**

Application/Control No.

10/784,806

Applicant(s)/Patent Under  
Reexamination  
KIM ET AL.

Examiner

Sin J. Lee

Art Unit

1752

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**U.S. PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-6,667,243 B1	12-2003	Ramsbey et al.	438/710
	B	US-4,732,838	03-1988	Sechi et al.	430/198
	C	US-			
	D	US-			
	E	US-			
	F	US-			
	G	US-			
	H	US-			
	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

**FOREIGN PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N					
	O					
	P					
	Q					
	R					
	S					
	T					

**NON-PATENT DOCUMENTS**

Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)

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	U	Kim et al "Nonshrinkable Photoresists for ArF Lithography", Advances in Resist Technology and Processing XX, Proceedings of SPIE Vol.5039 (2003), pg.689-697.
	V	
	W	
	X	

\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
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